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PATENT

Docket No. 150.00800102

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Brian A. Vaartstra ) Group Art Unit: 1756  
Serial No.: 09/651,702 ) Examiner: N. Barreca  
Confirmation No.: 2471 )  
Filed: August 30, 2000 )  
For: SUPERCRITICAL COMPOSITIONS FOR REMOVAL OF ORGANIC MATERIAL  
AND METHODS OF USING SAME

FAX RECEIVED  
JUN 23 2003  
TC 1700AMENDMENT AND RESPONSE

Assistant Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

In response to the Office Action mailed March 20, 2003, please amend the above-identified application as follows:

In the Specification

Please replace the paragraph beginning at page 25, line 5 (i.e., Abstract of the Disclosure), with the following rewritten paragraph. Per 37 C.F.R. §1.121, this paragraph is also shown in Appendix A with notations to indicate the changes made.

-A method for removing organic material in the fabrication of structures includes providing a substrate assembly having an exposed organic material and removing at least a portion of the exposed organic material using a composition including sulfur trioxide (SO<sub>3</sub>) in a supercritical state. For example, the exposed organic material may be selected from the group of resist material, photoresist residue, UV-hardened resist, X-ray hardened resist, carbon-fluorine containing polymers, plasma etch residues, and organic impurities from other processes.

Further, organic material removal compositions for performing such methods are provided/